

Notice of References Cited	Application/Control No. 10/683,727	Applicant(s)/Patent Under Reexamination SHERMAN, ARTHUR	
	Examiner Kelly Stouffer	Art Unit 1762	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-4,949,671	08-1990	Davis et al.	118/725
*	B	US-4,882,008	11-1989	Garza et al.	216/48
	C	US-			
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Dillon, AC et al. "Surface chemistry of Al ₂ O ₃ deposition using Al (CH ₃) ₃ and H ₂ O in a binary reaction sequence" Surf. Sci. 322 (Jan 1995) 230-242.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.